

# ECE 327: *Electronic Devices and Circuits Laboratory I*

## Notes for Lab 2 (Field Effect Transistor Lab)

### 1. Trans-istor: transconductance (variable) resistor

- Bipolar (“accident”) and unipolar (FET, “valve”, like “tube”) varieties
  - New technologies share features of both (e.g., insulated gate bipolar transistors (IGBTs))
- **Voltage**-controlled current sources (VCCS)
  - Vary *channel resistance* in order to make current constant
  - Think of “transistor man” from Horowitz and Hill (1989)
- For a bipolar transistor, base–emitter diode is forward biased, so it carries current too. So

$$i_B = I_S \left( \exp \left( \frac{v_{BE}}{kT/q} \right) - 1 \right) \quad \text{where } \frac{kT}{q} \approx 25.3 \text{ mV @ room temperature}$$

and

$$i_C = \beta I_S \left( \exp \left( \frac{v_{BE}}{kT/q} \right) - 1 \right) = \beta i_B$$

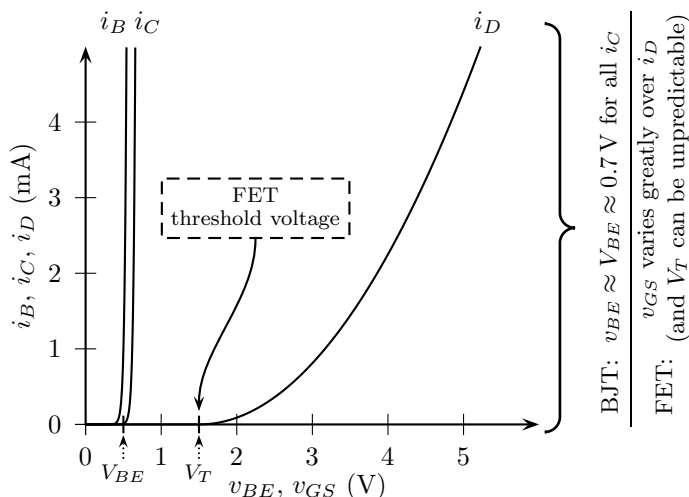
where  $I_S \approx 0$  and  $\beta \gg 1$  are determined by material properties. Fortunately,  $i_C = \beta i_B$ . This relationship and the (steep) exponential  $i$ - $v$  curves help make the bipolar transistor so handy.

- For a unipolar transistor (FET), no current enters the gate. So  $i_G = 0$  and

$$i_D = K (v_{GS} - V_T)^2$$

where  $0.5 \text{ V} < V_T < 10 \text{ V}$  and (small)  $K$  are determined by material properties and temperature.

- Graphically:



- Notice vertical scale. Consider  $v_{GS}$  required for a *significant* drain current
- Additionally, threshold  $V_T$  can have a 5 V manufacturing spread (!!)
- NOTE: In tiny region below  $V_T$ , unipolar has steep exponential curve similar to bipolar

- BJTs: high transconductance (+), very non-linear curve (–), *predictable* base–emitter drop (+?)

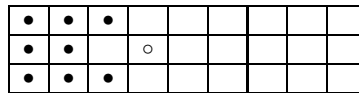
2. Analogous operation modes (gate  $\sim$  base, source  $\sim$  emitter, drain  $\sim$  collector):

| Condition                | $\implies$ | Unipolar (FET)                    | $\sim$ | Bipolar (BJT) |
|--------------------------|------------|-----------------------------------|--------|---------------|
| Low gate–source voltage  | $\implies$ | “Subthreshold”                    | $\sim$ | “Cutoff”      |
| High gate–source voltage | $\implies$ | “Pinch-off” (or “Saturation”)     | $\sim$ | “Active”      |
| Low source–drain voltage | $\implies$ | “Linear” (or “Triode” or “Ohmic”) | $\sim$ | “Saturation”  |

- Bipolar and unipolar “saturation” are different (BJT: out of active mode, FET: into active mode)
- BJT “Saturation” versus FET “Ohmic” — only FETs can really be switches
  - Bipolar saturation is not practically usable (slow to exit, and can be impossible to use on IC)
  - In “Ohmic” mode, FET is like programmable resistor (e.g., electronic volume control, switches)

3. Diffusion reminder (demonstration: cold H<sub>2</sub>O, hot H<sub>2</sub>O, shaken H<sub>2</sub>O, tilted H<sub>2</sub>O (like diode))

- Diffusion is a statistical certainty (entropy increases)
  - Thermal agitation causes movement, but eventually “now” and “later” *look* identical
  - Movement is random, so clusters tend to spread out (i.e., “down” “diffusion gradient”)



If the ◦ is about to move or swap with a •, there is only a 1/8 chance that the result will be *more* concentrated. *Statistically* speaking, “order” tends to decrease (2<sup>nd</sup> law of thermodynamics).

4. Doping and the *pn*-junction

- Semiconductors are defined by their electron energies (not the same as “quasi-conductors”)
  - Empty conduction band (no “free” carriers in structure)
  - Small “band gap” between valence and conduction bands
  - Small excitation energy (e.g., heat) lets electrons move to conduction band (become mobile)
- Semiconductor lattices and doping
  - Covalent bonds (silicon has four)
  - Can insert impurities by “doping”
    - \* *Neutral* atom with one less bonding electron inserts a “hole” in lattice
    - \* *Neutral* atom with one more bonding electron
  - Extra electrons and holes *can move* through lattice (like positive and negative carriers)
    - \* A semiconductor with lots of extra holes is “p”-type because holes *repel* from “positive”
    - \* A semiconductor with lots of extra electrons is “n”-type because electrons are “negative”
  - Because there are always the same number of *protons* and *electrons*, the material is always *NEUTRAL*; however, *SPACE CHARGE* can develop as impurities move
- The *pn*-junction and the diode “rectifier” (like *ball check valve*)
  - Join a *p*-type material and an *n*-type material to setup *diffusion gradient*
    - \* Holes from *p*-type will diffuse into *n*-type
    - \* Electrons from *n*-type will diffuse into *p*-type
  - Electric field builds up that stops diffusion (like weighted marbles tilting a balanced see-saw)
    - \* Extra holes in *n*-type setup a positive charge, which repels additional holes
    - \* Extra electrons in *p*-type setup a negative charge, which repels additional electrons
  - By applying enough *opposing* field (i.e., apply positive to *p* side), **bipolar** diffusion will continue (like rebalancing the see-saw) — **bipolar current** from **holes AND electrons!**
    - \* Temperature-dependent “diode drop” (0.6–0.7 V at 300 K) is diffusion *barrier* energy

5. Bipolar (junction) transistor (BJT) device operation: **DIFFUSION** and *not* drift!
- Opposing *pn* junctions (diodes) in series ( $npn \approx np\text{-}pn$  and  $pnp \approx pn\text{-}np$ )
    - Forward bias base–emitter diode by  $\sim 0.7$  V causes **bipolar diffusion** of electrons **AND** holes
    - Reverse bias base–collector diode
    - Diffusion is a current *source* — New carriers in base from emitter must go somewhere
      - \* Active mode: When base–collector diode reverse biased, carriers are *collected* and exit
      - \* Saturation mode: Otherwise, exit from *base*; extra current causes 0.8 V base–emitter drop
    - Asymmetric: Emitter and collector have same *type* of doping, but different amount/size/shape
    - Diffusion current proportional to emitter–base junction area
  - *Very fast*
    - New special versions (HBTs) operate at terahertz (THz) frequencies
    - For comparison, visible light starts around 750 THz
  - Price of bipolar:
    - Relatively high base current (“leakage”)
      - \* High input (base) current drive makes simple BJTs impractical for power applications
    - BJT size is practically limited (i.e., BJTs are “large” on a piece of silicon — costly)
6. Unipolar or *field effect* transistor (FET): **DRIFT** and *not* diffusion!
- In these devices, current flows through a conductive channel
    - Device is (principally) *symmetric*
    - *Source* and *drain* are ends of the channel
    - *Source*  $\approx$  *emitter* and *drain*  $\approx$  *collector*
      - \* For *n*-channel devices, “source” means more-**N**egative end (it *sources* electrons)
      - \* For *p*-channel devices, “source” means more-**P**ositive end (it *sources* holes/*sinks* electrons)
  - *Shape* of this channel can be changed by using a *field* to re-orient the charge carriers
    - Control voltage applied to a central *gate* (similar to “base”)
    - Device acts like a *valve*
    - Similar to vacuum tube (grid  $\sim$  gate, drain  $\sim$  plate, source  $\sim$  cathode/filament)
  - Voltage increases cross-sectional *area* of channel, so we expect squared  $v$ - $i$  relationship (quadratic)
  - FET vs BJT:
    - very high input impedance (low leakage) (+), much smaller footprint/scalable/cheaper (+)
    - high input capacitance (–), slow (–)
  - The *Junction* FET (JFET): A depletion-mode device
    - A diode (*pn*-junction) “on its side” (symbol, often symmetric, looks like sideways diode)
      - \* Symbol depicts channel type (*p/n*); arrow is a “diode” that points toward *n* of *pn*-junction
      - \* “Diode” should always be reverse biased; amount of bias determines channel shape
    - Channel is shaped by reverse bias
      - \* If drop across channel is low, channel acts as resistance controlled by reverse bias
      - \* If drop across channel is high, channel gets triangular, and current “pinches off”
    - “Pinch off” mode acts as current source by *preventing* additional current
      - \* By Ohm’s law, any more current would create a greater drop across channel
      - \* The additional reverse bias at drain side of channel would cut-off current completely
      - \* So expect an equilibrium current
      - \* Changing channel cross-section with gate voltage changes equilibrium current
    - A JFET channel exists until reverse bias takes it away; they’re “depletion-mode” devices
      - \* Current flows “normally” (with gate–source shorted)
      - \* By applying field, we “deplete” the channel to turn current *off*
    - Relative to MOSFETs, JFETs are fast but have high leakage ( $< 100$  pA)

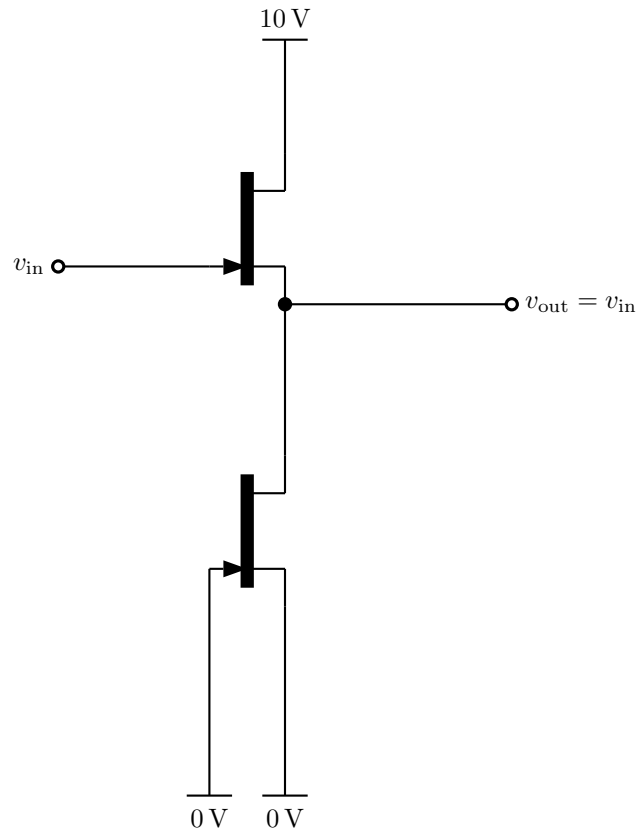


Figure L2-1: JFET source follower using matched JFETs.

- Clever example: JFET source follower in [Figure L2-1](#)
  - \* JFETs must be matched on the same piece of silicon
  - \* Both JFETs are depletion-mode devices
  - \* Bottom JFET is a current source (pinched-off channel at maximum size)
  - \* Same current flows through top JFET, so its gate and source differ by the same as the bottom gate and source
  - \* **Hence, the output follows the input *exactly* (no diode drops!)**
  - \* Reminder: Followers are used as voltage buffers
  - \* For a wide range of output currents, the output voltage stays the same
  - \* In other words, the output has *very low impedance* ( $\Delta V / \Delta I \approx 0$ ; think Thévenin)

## 7. Metal-Oxide-Semiconductor FET (MOSFET) or Insulated-Gate FET (IGFET)

- Look like symmetric BJT
  - $n$ -channel: two  $n+$  regions separated by a  $p$  region
  - $p$ -channel: two  $p+$  regions separated by an  $n$  region
- Middle region is “bulk” or “body”
  - Bulk–source junction must be reverse biased
  - Common (e.g., in power applications) to short bulk to one end of channel
    - \* Forces that end of channel to be *source*
    - \* Introduces a diode between drain and source
    - \* *MUST* be sure to keep drain–source reverse biased
  - Otherwise, short bulk to appropriate DC *rail* (e.g., high for  $p$ -channel and low for  $n$ -channel)
    - \* No difference between source and drain
    - \* Bidirectional current: great for switching applications
- “Gate” separated from bulk by oxide (rust,  $\text{SiO}_2$ ) *insulator*
  - Gate-oxide-bulk form MOS capacitor (gate: **M**etal, insulator: **O**xide, bulk: **S**emiconductor)
  - **DIELECTRIC BREAKDOWN** of oxide is both fatal and easy to induce
  - Gate–bulk field controls channel
    - \* Pulls/pushes excess carriers from/to *both* drain and source
    - \* Eventually, bulk region near gate gets *inverted* to other type
    - \* For low drain–source drop, uniform channel acts as gate–controlled resistor
    - \* For high drain–source drop, triangular channel “pinches off” current at constant value
- Enhancement and depletion varieties exist
  - Enhancement: add a field to turn *on* current
  - Depletion: add a field to turn *off* current
- In ohmic mode, low channel resistance and bidirectionality makes them great *switches!*
- In a small space (cheap!!), can mimic (e.g., switching, ohmic, etc.) all *larger* passive components
- Standard symbol: Shows insulated gate (MOS capacitor)
  - Channel: dashed or solid
    - \* dashed: enhancement (“normally off”)
    - \* solid: depletion (“normally on”)
  - Arrow: Diode formed by channel
    - \* Points toward  $n$  region (channel or bulk)
- Alternative symbol: BJT-like ( $n$ -channel is **not** pointing in; etc.)
  - Thick depletion channel; Thin enhancement channel
- Alternative symbol: Digital “switch”
  - Logic high turns  $n$ -channel on
  - Logic low turns  $p$ -channel on (bubbled symbol)
  - All enhancement mode
- Using MOSFETs and BJTs
  - Common-gate, common-drain, and common-source work like analogous BJT configurations
  - MOSFETs have high gate capacitance and are slow, but have negligible gate leakage ( $< 10$  pA)
  - Unlike BJT, can swing from rail to rail (no diode drops to worry about)
  - IC designers can control MOSFET properties by adjusting geometry and oxide capacitance

## 8. Complementary or Complementary-Symmetry MOS (CMOS)

- Use  $n$ -channel and  $p$ -channel MOSFETs together in exactly equal and opposite ways
- Low-power device — high input impedance and no current in digital operation
- Because of high gate capacitance, power becomes a problem at high frequencies ( $V^2 C f$ )
  - Modern microprocessors have high FET count, so have high capacitance
  - Modern microprocessors are very fast (for absolutely no good *technical* reason)
  - Easily hit 2 kW with 30 M transistors at 4 GHz (!!!!)
  - Trick: Lower  $V$

9. **Example:** CA3130 (uncompensated) BiMOS operational amplifier — schematic from [datasheet](#)

- Recall: Operational amplifier is differential amplifier with (nearly) *infinite gain*
  - CA3160 is identical, but has *internal* compensation capacitor for unity-gain stability
- Combines BJTs and MOSFETs
  - FETs: Minimal input leakage; maximal “rail-to-rail” output swing
  - BJTs: Give very *high gain* and *high speed*
    - \* Notice common-emitter amplifier with *current source* at collector (“dynamic load”)
    - \* Current source has high impedance ( $\Delta I / \Delta V \approx 0$ ; think Thévenin)
    - \* Common-emitter gain is collector impedance divided by emitter impedance ( $\infty / \text{tiny} \approx \infty$ )
  - Current source implemented with (Cascode configuration) MOSFET current mirror
    - \* **Cascode**: Common-source followed by common-gate (yes, cascode, with an “o”)
    - \* “**Cascode**” historically describes an “**cascaded triode**”, an alternative to a “pentode”
      - Traditional “cascades” connect plate anode (“drain”) to grid (“gate”) to magnify gain.
      - A “cascode” “**cascades**” a plate **anode** (“drain”) with a filament **cathode** (“source”).
    - \* Here, common-source sets current (by mirror) and common-gate buffers current
    - \* Prevents channel-length modulation (like BJT Early effect) and Miller effect
  - Output stage is **CMOS inverter** operated in linear range (i.e., as *class-A amplifier*)
  - **NOTE:** Gate-oxide protection diodes (breakdown harmlessly and short out static discharge)

## 10. Laboratory experience (CMOS inverter, integrator review, switched-capacitor integrator)

- Be very careful with MOS parts!
  - MOS parts:
    - \* CD4007 (3 CMOS pairs), CD4066 (4 CMOS analog switches), CD4049 (6 CMOS inverters), CA3160 (compensated BiMOS operational amplifier)
  - Static discharge can fry gate oxide (i.e., dielectric breakdown)
  - Keep one hand on breadboard metal when other hand is installing MOS chip
  - **DO NOT** install chip when power is on!
  - **DO NOT** forget to wire-up power rails. In fact, **DO IT FIRST!!!**
    - \* Power on *circuit* **before** signal source; turn *off* **signal source** *before* powering off circuit.
  - When debugging problems, test parts in isolation
  - If one component on a part is not working, try a different component on the same part
- Use handouts for guidance on particular circuits
  - Detailed laboratory procedures (and pin-outs)
  - Continuous-time integrator schematics and explanations
- Follow lab *book* (detailed instructions in supplementary text)
- **DO NOT** disassemble continuous-time integrator! It is used in the switched-capacitor circuit!
- When taking plots, save as CSV or BMP (or snap a CLEAR picture)
  - Show units; label axes; identify waveforms (e.g., “input”); show horizontal/vertical divisions
  - In most cases, channel grounds should be shown